



Pivotal Systems Awarded First Key Patent for Gas Flow Monitoring

PATENT ESTABLISHES PIVOTAL AT THE FOREFRONT OF GAS FLOW CONTROL FOR THE SEMICONDUCTOR INDUSTRY

Pleasanton, CA. – December 10 , 2010—Pivotal Systems Corporation, the leader in advanced process monitoring and control solutions, today announced it was awarded its first worldwide patent for its Gas Flow Monitoring (GFM) technology. With a number of leading IDMs and foundries adopting GFM for advanced node manufacturing, this initial patent establishes Pivotal at the forefront of innovation in gas flow monitoring and control.

“As strategic partners, the top IDMs and foundries have been telling us for some time now that gas flow control is becoming increasingly problematic for process control and chamber matching,” said Mukund Venkatesh, Pivotal’s VP of Marketing. “The industry’s best mass flow controllers are struggling to meet the accuracy, settling time and repeatability specs required for 32nm and beyond.” The key differentiating features of GFM are its ability to take in situ measurements during wafer processing with high accuracy ($\pm 0.5\%$) and at a high sampling rate (for MFC transient / settling time analysis).

“Pivotal’s efforts in gas flow monitoring and control started in 2006 and we are excited to have this first patent,” said Joseph Monkowski, Pivotal’s CTO. “We strive to innovate and develop solutions that are intuitive and easy to install. With GFM, the challenge was implementing a rate of drop pressure measurement during wafer processing without affecting the wafer process and within the confines of existing gas panel systems.”

John Hoffman, Pivotal’s CEO pointed out that this is Pivotal’s fourth issued patent. “The GFM technology and approach is at the core of many more patent applications and an integral part of our soon to be released Gas Flow Controller - which promises an order of magnitude improvement on existing mass flow controllers in terms of accuracy, range, and settling time.”

About Pivotal Systems

Pivotal Systems Corporation provides best-in-class monitoring and process control technology for the semiconductor manufacturing industry. Pivotal’s vision is to enable an order of magnitude increase in fab productivity and capital efficiency for current and future technology nodes. This vision is achieved through its real time in situ process monitoring and control solutions. Founded in 2003 and based in Pleasanton, California, the company is led by veterans from the semiconductor and high-tech industries. For more information about Pivotal, please visit www.pivotalsys.com, or send an email to info@pivotalsys.com.